

FIG. 1A  
PRIOR ART

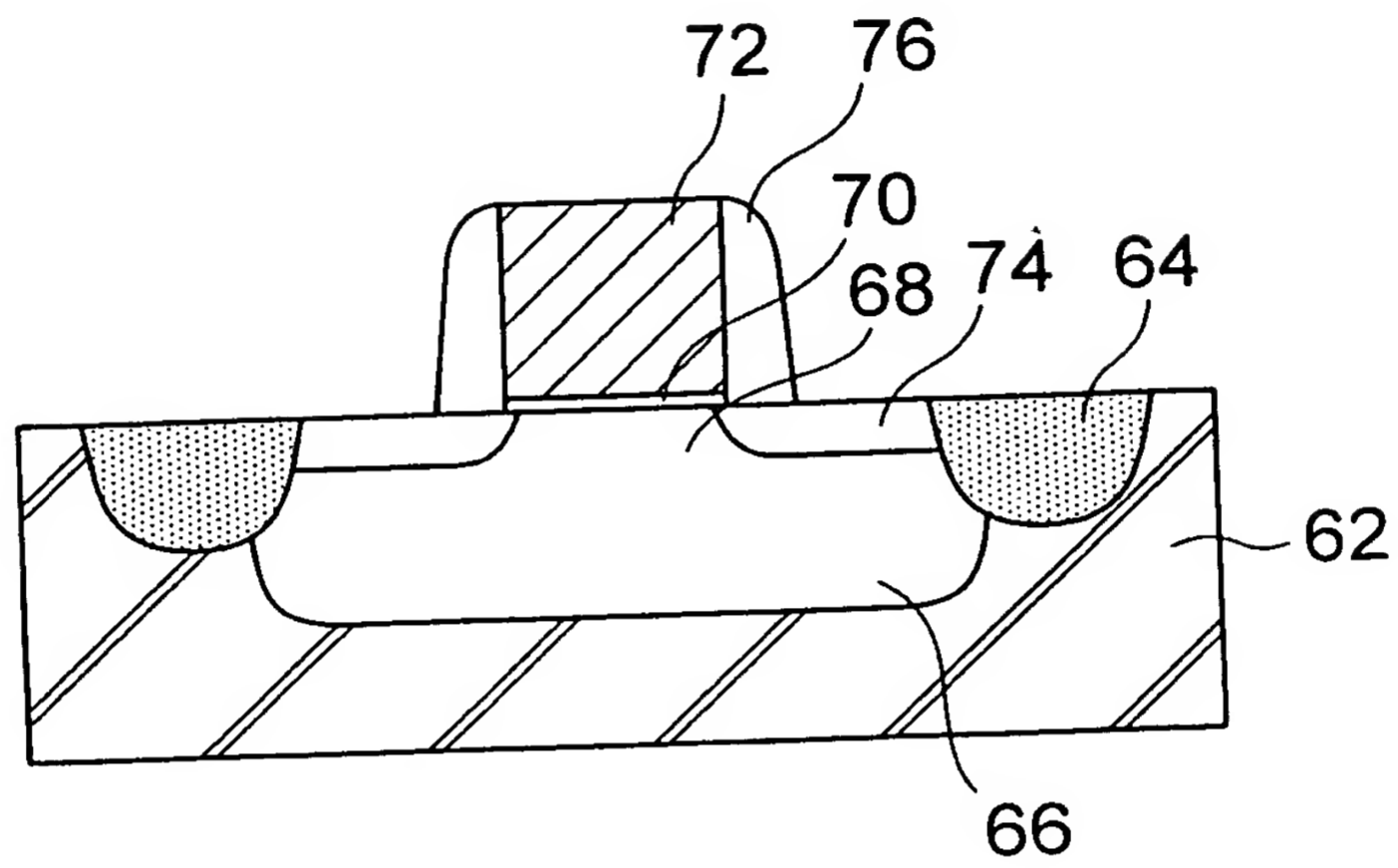
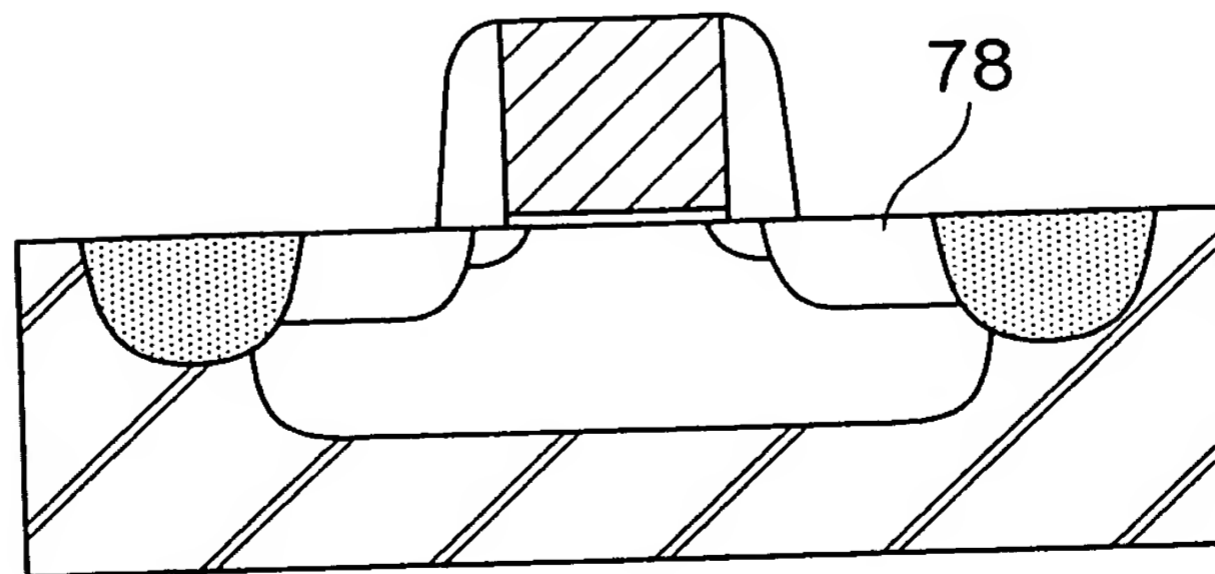
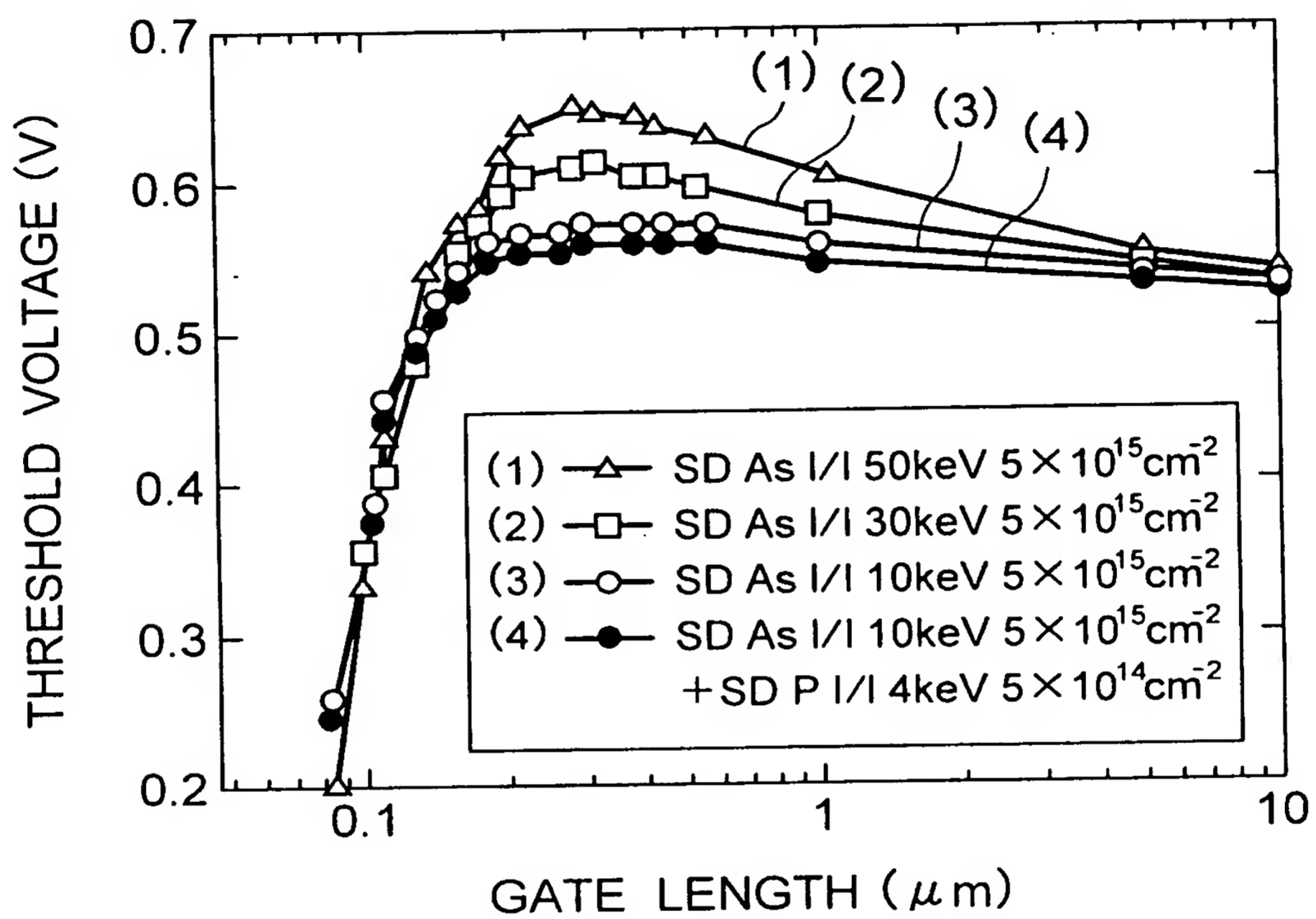


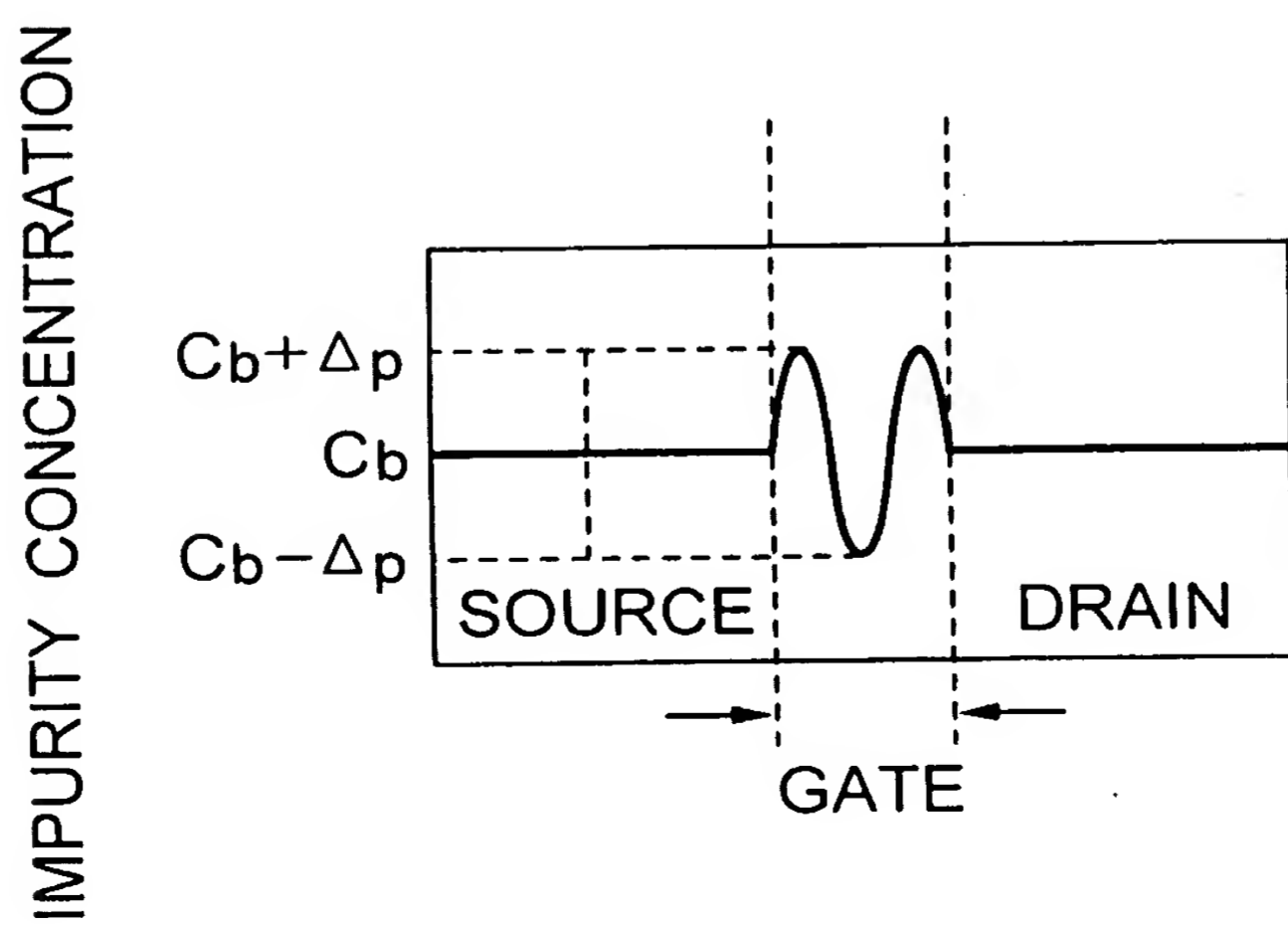
FIG. 1B  
PRIOR ART



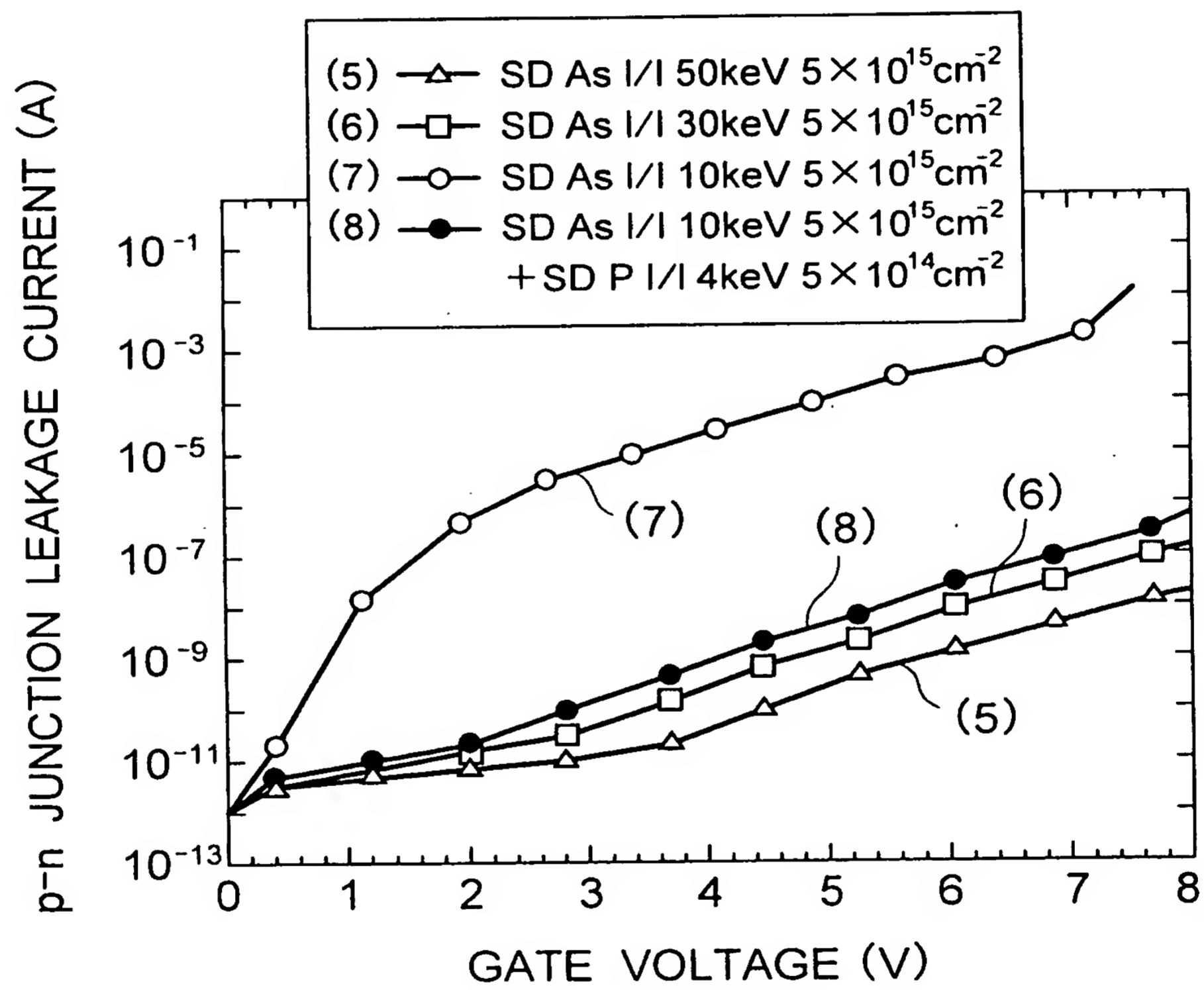
# FIG. 2



# FIG. 3



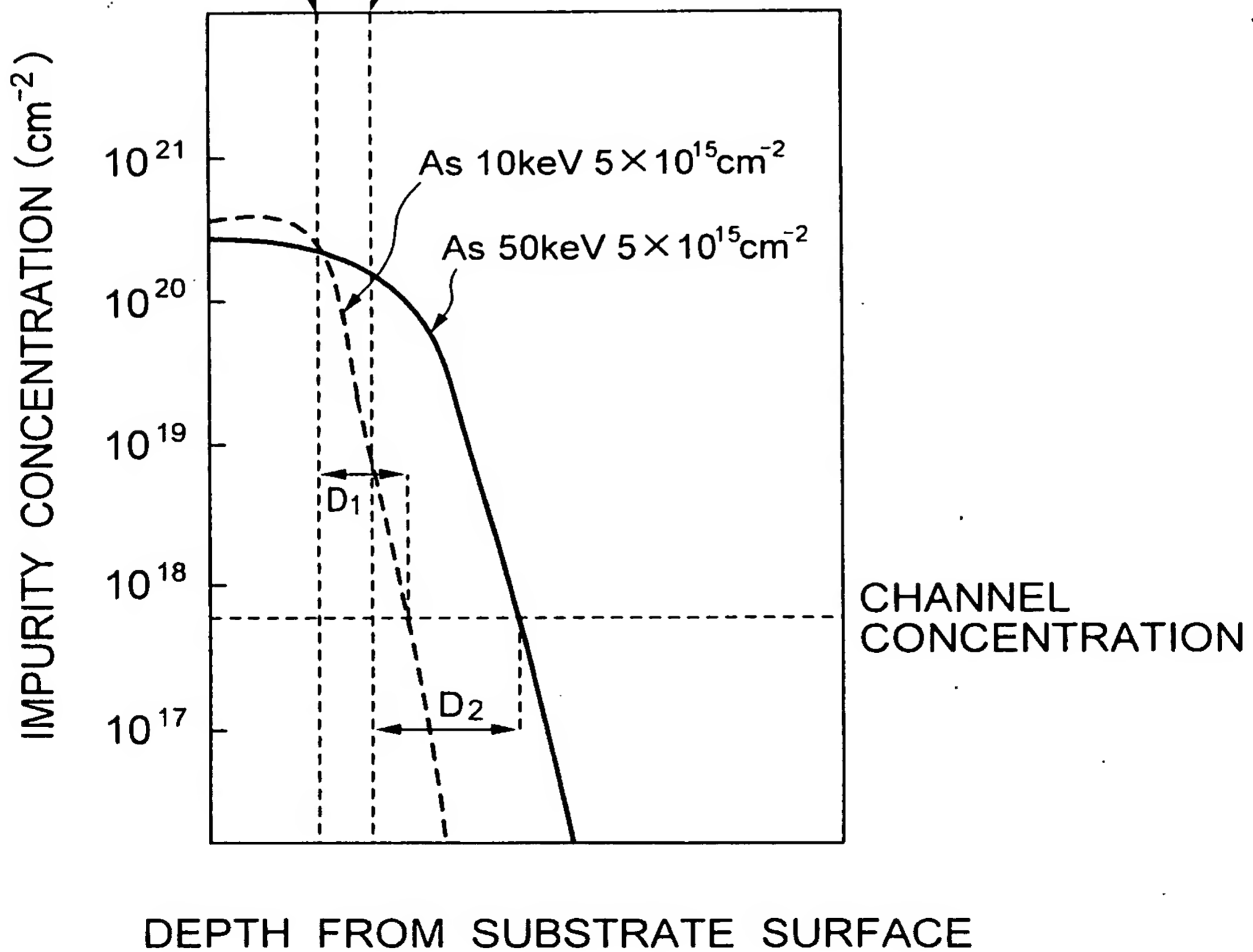
# FIG. 4



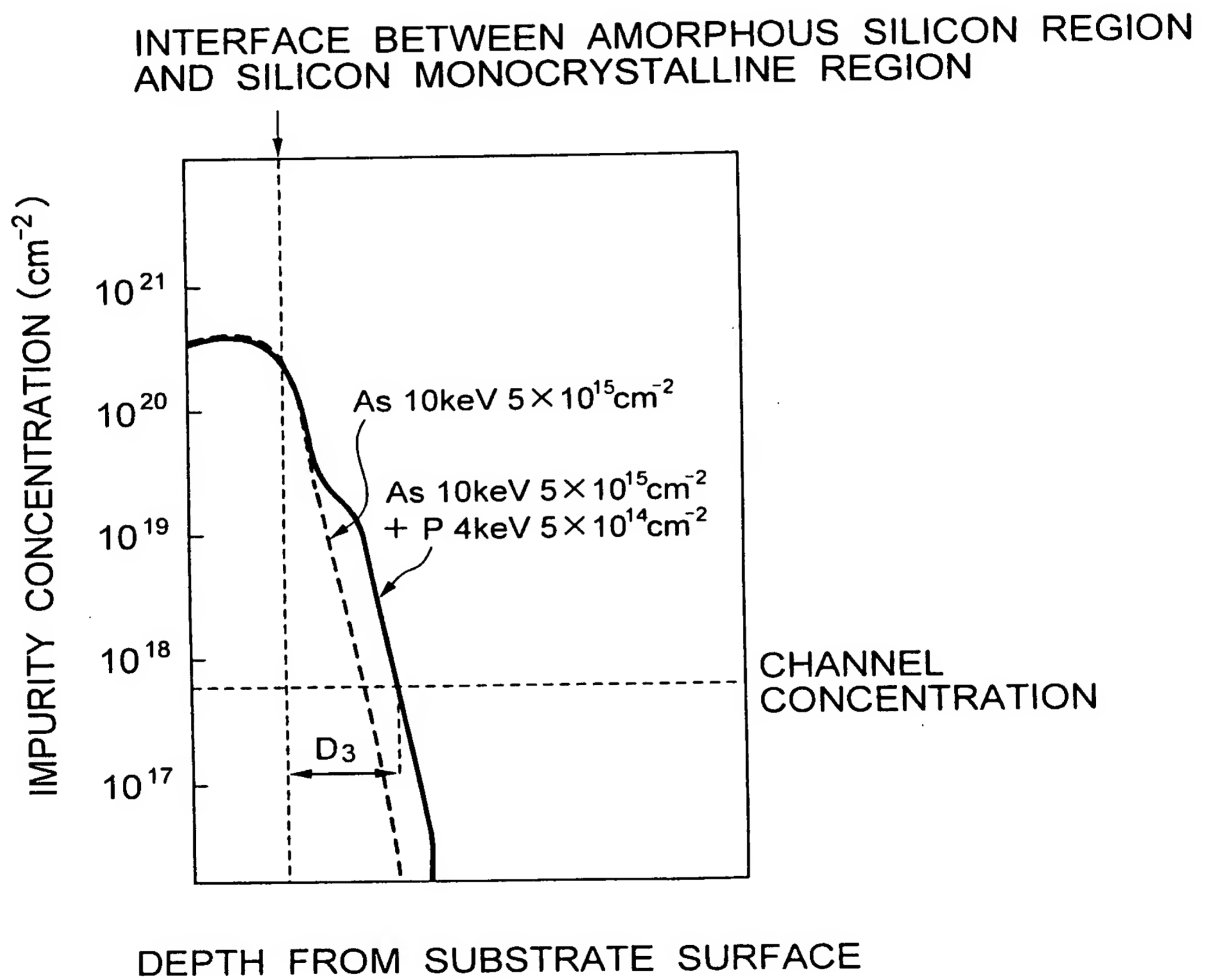
# FIG. 5

INTERFACE BETWEEN AMORPHOUS SILICON  
REGION AND SILICON MONOCRYSTALLINE  
REGION WHEN As IS IMPLANTED AT  
10keV AND  $5 \times 10^{15} \text{ cm}^{-2}$

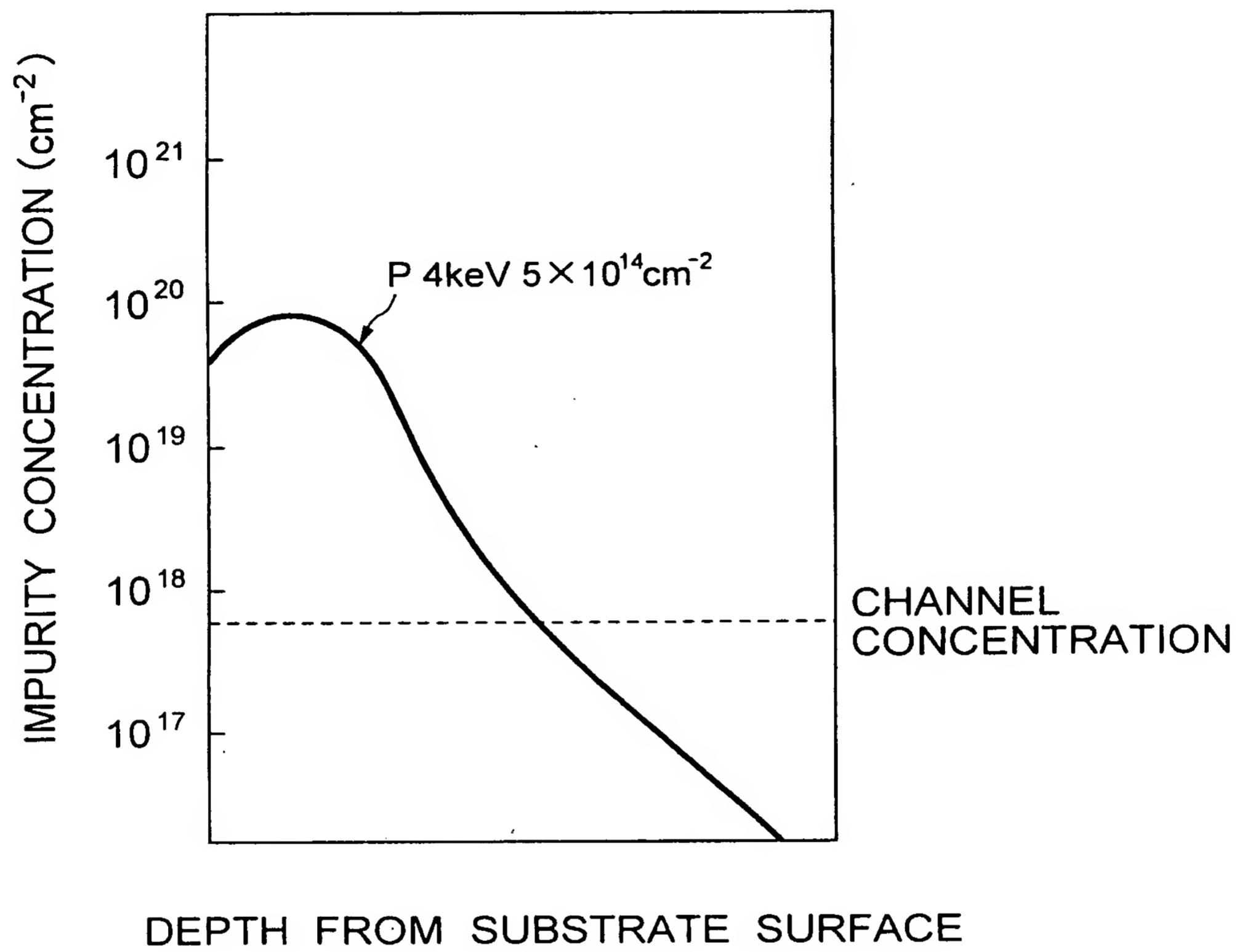
INTERFACE BETWEEN AMORPHOUS SILICON  
REGION AND SILICON MONOCRYSTALLINE  
REGION WHEN As IS IMPLANTED AT  
50keV AND  $5 \times 10^{15} \text{ cm}^{-2}$



# FIG. 6



# FIG. 7



# FIG. 8

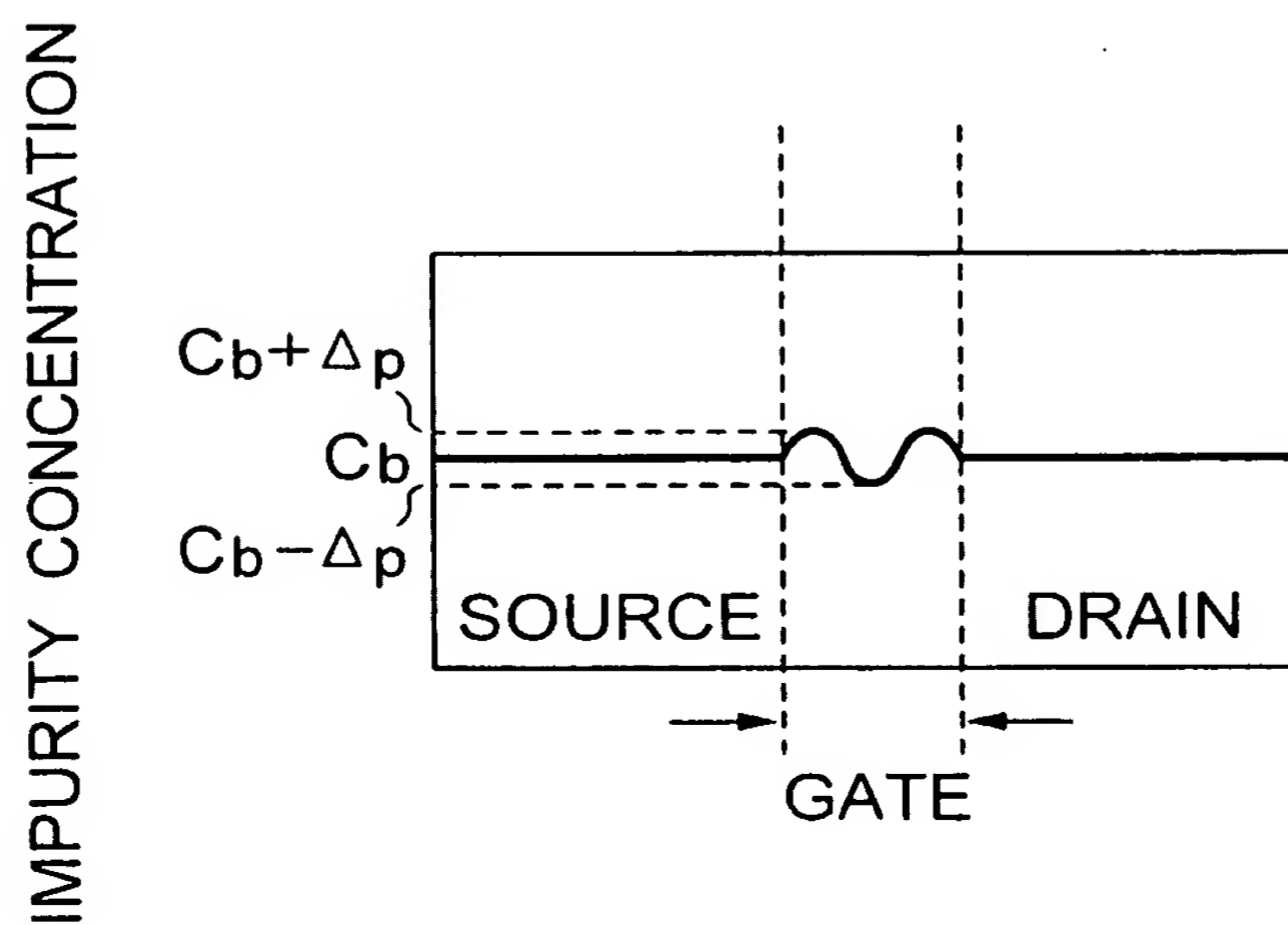
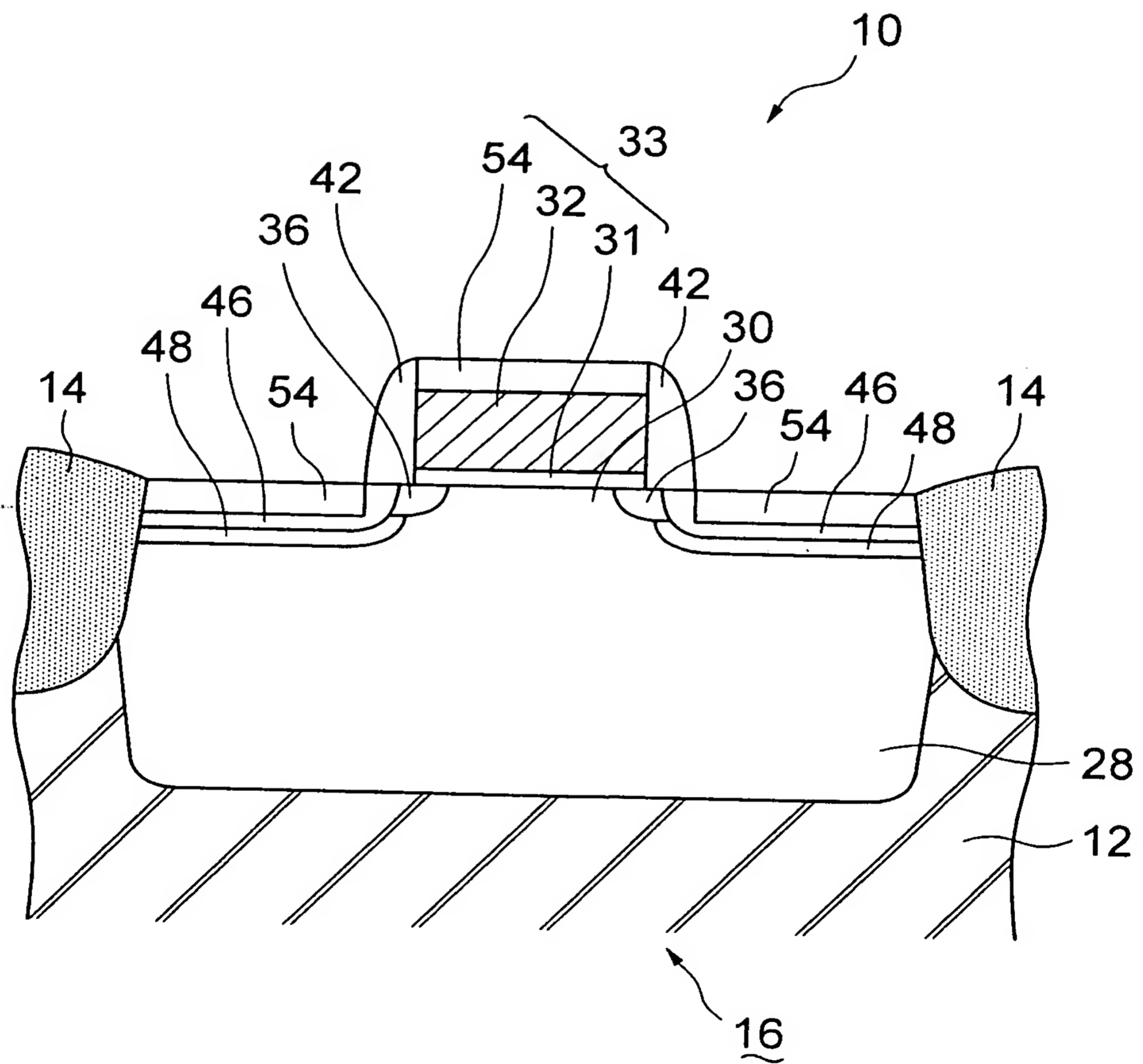
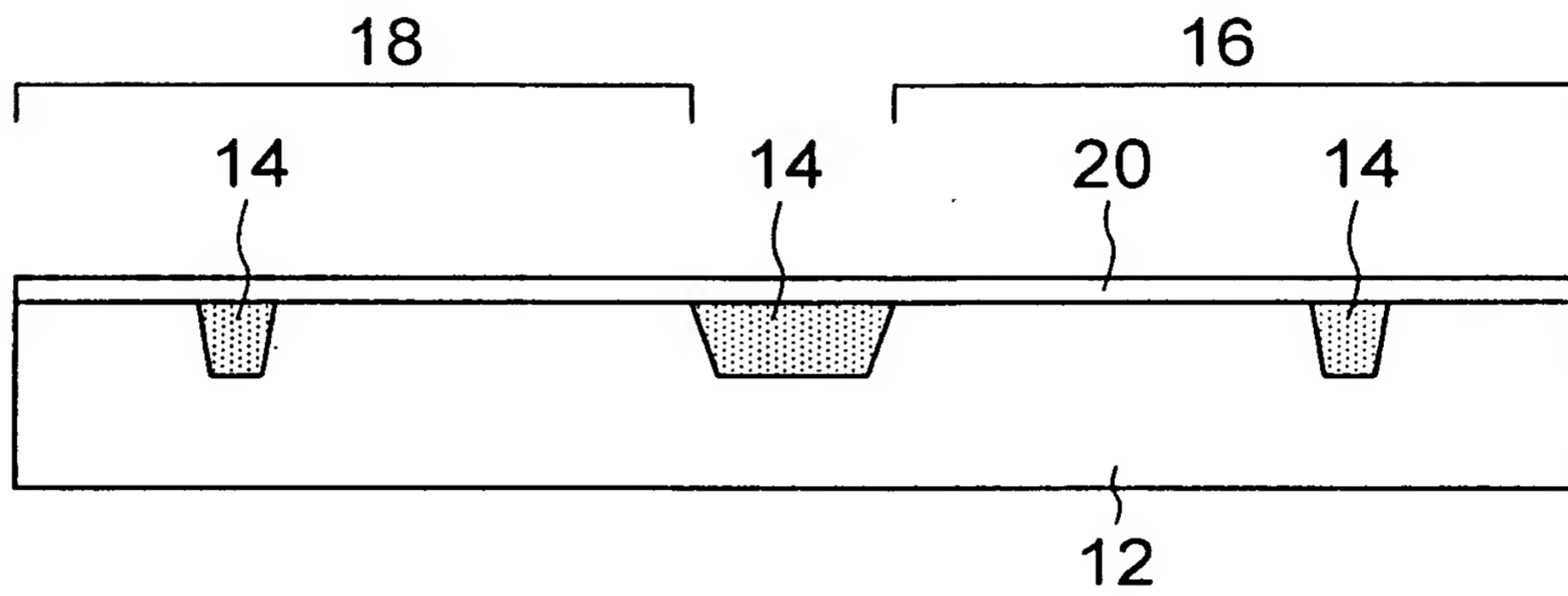


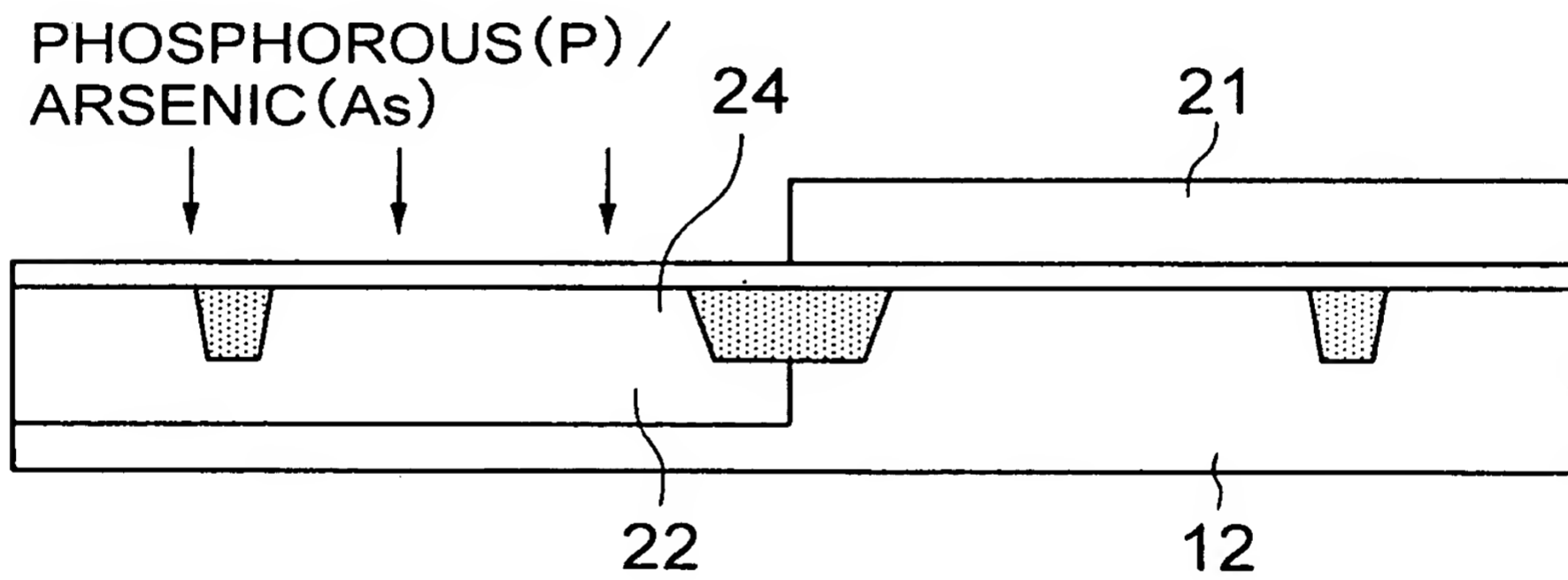
FIG.9



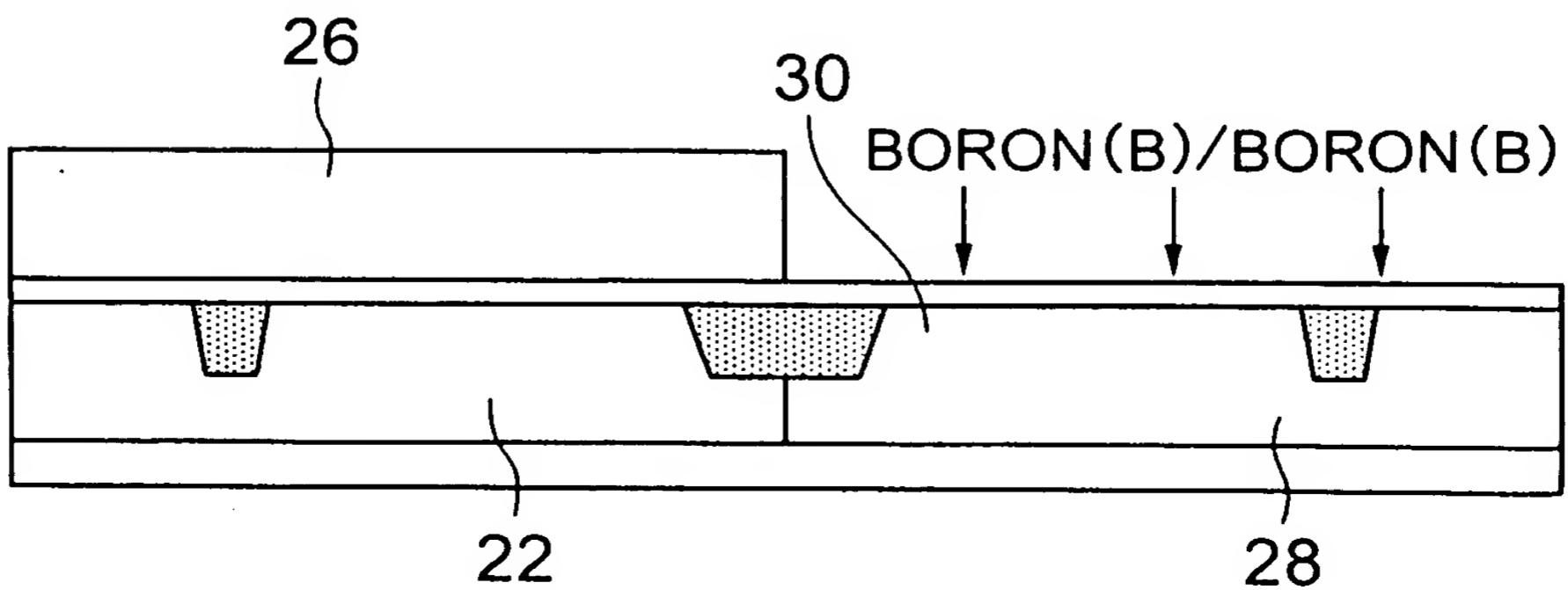
# FIG.10A



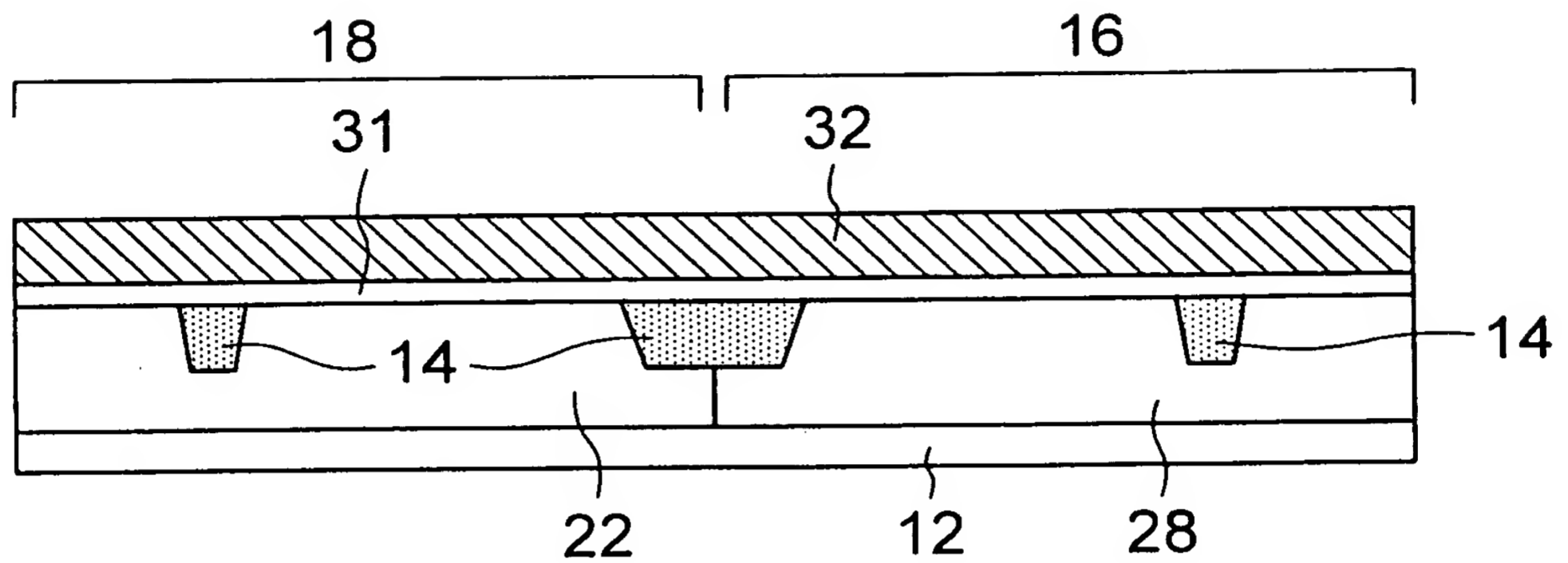
# FIG.10B



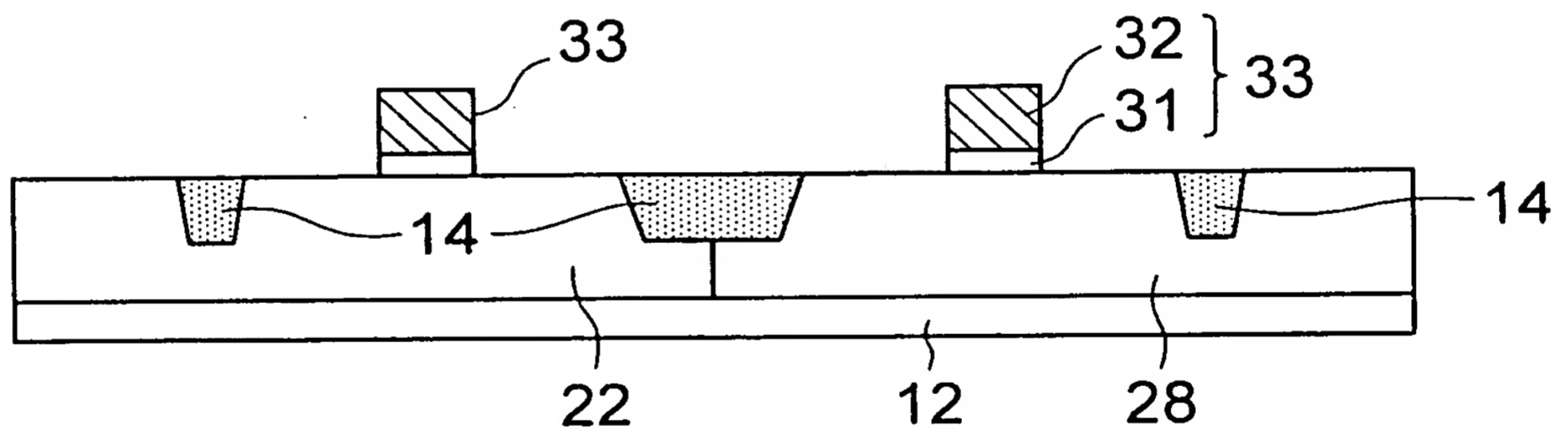
# FIG.10C



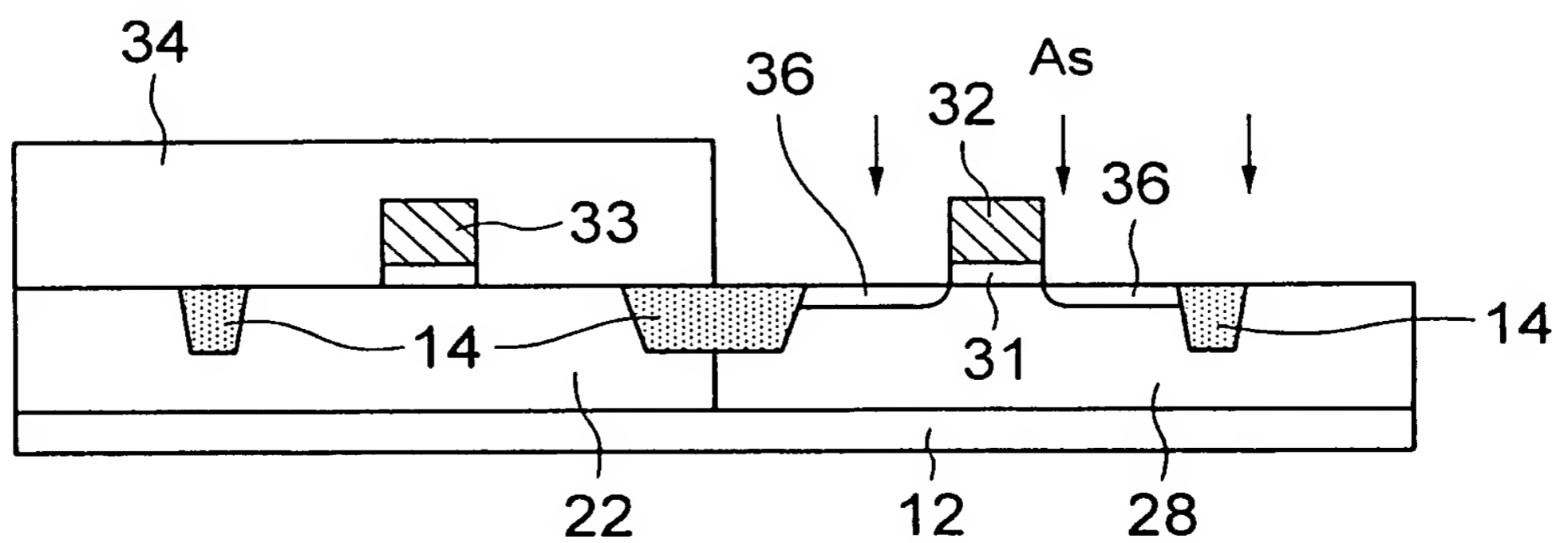
# FIG.10D



# FIG.10E



# FIG.10F



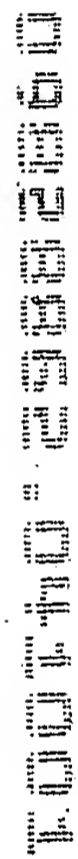
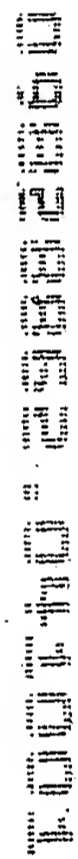
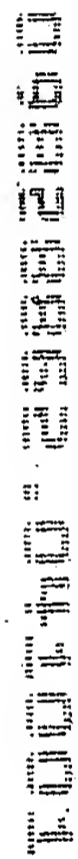
[illegible][illegible]

FIG.10J

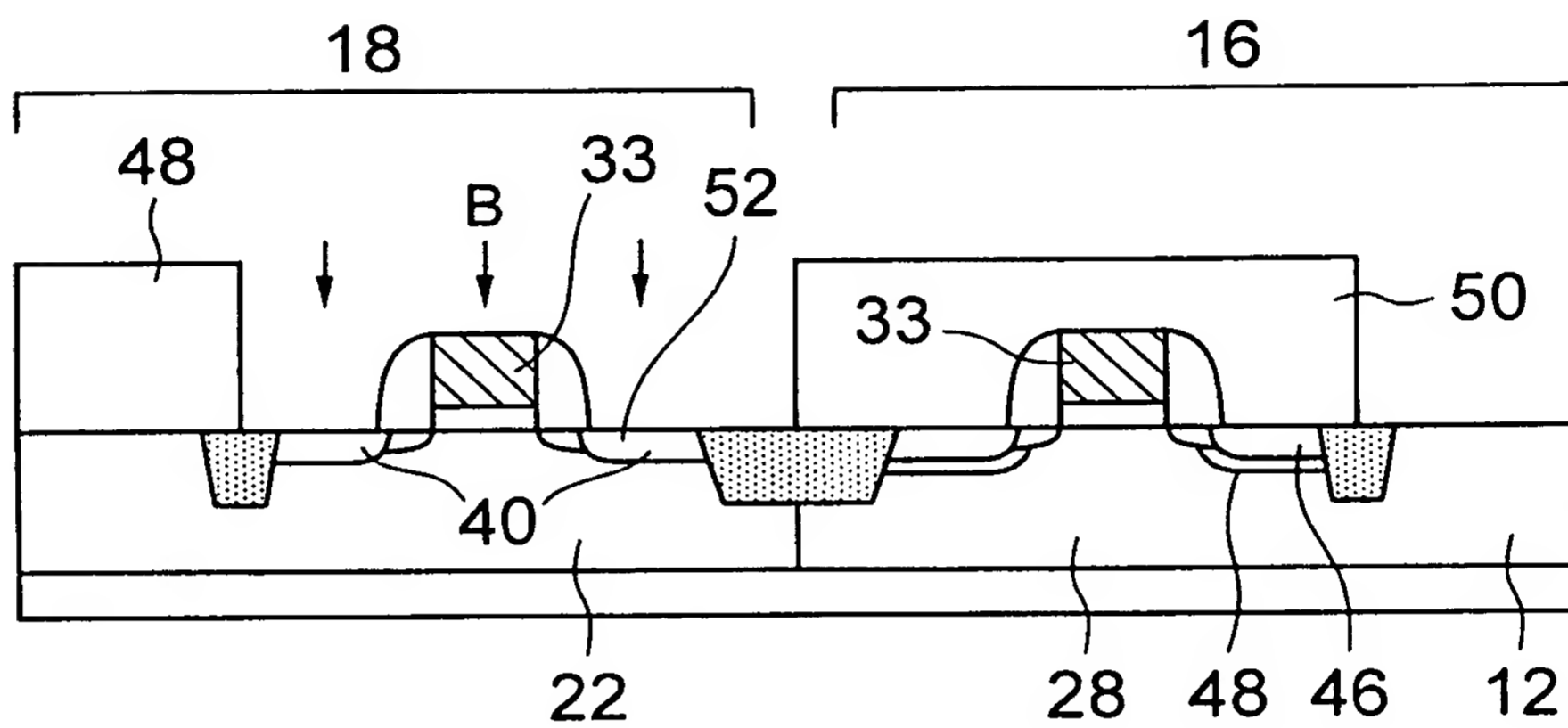


FIG.10K

